

	Hits	Search Text
4	514	(mask\$3 or photomask or reticle) and ((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive)) and (mask\$3 same opening) and (dry\$4 or heat\$4 or anneal\$7) and (solidifying or solidify) and pattern
5	140	(mask\$3 or photomask or reticle) and ((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive)) and (mask\$3 same opening) and (dry\$4 or heat\$4 or anneal\$7) and (solidifying or solidify) and pattern and evaporat\$4 and (remov\$4 same adher\$3 same3 (liquid or material or solute)) and ((remov\$3 or detach\$3) same mask same (substrate or wafer))
6	4	((mask\$3 or photomask or reticle) same ((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive)) same (coat\$3 or spray\$3coat\$3 or spin\$4coat\$3 or mist\$4coat\$3) same pattern\$4 same ((mask\$3 same opening) or transmiss\$6)) and ((dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify) same evaporat\$4) and (remov\$4 same adher\$3 same3 (liquid or material or solute)) and ((remov\$3 or detach\$3) same mask same (substrate or wafer))
7	2	("6599582") or ("20020067400").PN.
8	1	("6365531").PN.

	Hits	Search Text
9	9	(mask\$3 or photomask or reticle) and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive)) same (deposit\$4 or coat\$4 or layer) same (mist\$4 or atomi\$4 or (shower near4 head)) same (selective\$3 or (mask\$3 same opening))) and (dry\$4 or heat\$4 or anneal\$7 or evaporat\$4) and (hardening or curing or solidify\$3 or solidification) and pattern and ((remov\$4 or clean\$4) same3 (liquid or material or solute or excess) same mask) and ((remov\$3 or detach\$3 or strip\$4) same mask same (substrate or wafer))
10	501	(mask\$3 or photomask or reticle) and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive) or ((coat\$4 or film or liquid) near5 dispersion)) same (mask\$3 or lyophobic or lyophilic or hydrophobic) same (dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify or cure or curing) same pattern\$4) and (plural\$5 or second or dual or multipl\$2) same (coat\$4 or deposit\$4 or heat\$3 or anneal\$3 or (strip\$4 near5 mask\$3))

	Hits	Search Text
11	501	(mask\$3 or photomask or reticle) and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive) or ((coat\$4 or film or liquid) near5 dispersion)) same (mask\$3 or lyophobic or lyophilic or hydrophobic) same (dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify or cure or curing) same pattern\$4) and ((plural\$5 or second or dual or multipl\$2) same (coat\$4 or deposit\$4 or heat\$3 or anneal\$3 or (strip\$4 near5 mask\$3)))
12	67	(mask\$3 or photomask or reticle) and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive) or organic) same (mask\$3 or lyophobic or lyophilic or hydrophobic or pattern) same (dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify or cure or curing) same ((curtain near4 coat\$4) or spin\$3coat\$4 or dip\$3coat\$4)) and ((plural\$5 or second or dual or multipl\$2) same (coat\$4 or deposit\$4 or heat\$3 or anneal\$3 or (strip\$4 near5 mask\$3)))

	Hits	Search Text
13	5	430/322.ccls. and (mask\$3 or photomask or reticle) and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive) or ((coat\$4 or film or liquid) near5 dispersion)) same (mask\$3 or lyophobic or lyophilic or hydrophobic) same (dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify or cure or curing) same pattern\$4) and ((plural\$5 or second or dual or multipl\$2) same (coat\$4 or deposit\$4 or heat\$3 or anneal\$3 or (strip\$4 near5 mask\$3)))
14	14	430/311.ccls. and (mask\$3 or photomask or reticle) and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive) or ((coat\$4 or film or liquid) near5 dispersion)) same (mask\$3 or lyophobic or lyophilic or hydrophobic) same (dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify or cure or curing) same pattern\$4) and ((plural\$5 or second or dual or multipl\$2) same (coat\$4 or deposit\$4 or heat\$3 or anneal\$3 or (strip\$4 near5 mask\$3)))

	Hits	Search Text
15	127	"430"/\$.ccls. and (mask\$3 or photomask or reticle) and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive) or ((coat\$4 or film or liquid) near5 dispersion)) same (mask\$3 or lyophobic or lyophilic or hydrophobic) same (dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify or cure or curing) same pattern\$4) and ((plural\$5 or second or dual or multipl\$2) same (coat\$4 or deposit\$4 or heat\$3 or anneal\$3 or (strip\$4 near5 mask\$3)))
16	1	427/447.ccls. and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive) or ((coat\$4 or film or liquid) near5 dispersion)) same (mask\$3 or lyophobic or lyophilic or hydrophobic) same (dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify or cure or curing) same pattern\$4) and ((plural\$5 or second or dual or multipl\$2) same (coat\$4 or deposit\$4 or heat\$3 or anneal\$3 or (strip\$4 near5 mask\$3)))

	Hits	Search Text
17	64	"427"/\$.ccls. and (((pattern\$4 near3 material) or resist or photoresist or (radiation near3 sensitive) or ((coat\$4 or film or liquid) near5 dispersion)) same (mask\$3 or lyophobic or lyophilic or hydrophobic) same (dry\$4 or heat\$4 or anneal\$7) same (solidifying or solidify or cure or curing) same pattern\$4) and ((plural\$5 or second or dual or multipl\$2) same (coat\$4 or deposit\$4 or heat\$3 or anneal\$3 or (strip\$4 near5 mask\$3)))